

SPRINT for 50-200 fs / >200 kHz time resolved spectroscopy

*Advanced Photoelectric-effect Experiments – APE in Italian is also "bee" as well as the most versatile utility vehicle ever!



Publications

Days allocated to users

Total publications: 172

www.trieste.nffa.eu



Total days: 834

Involved institutions



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European Spin-OFF

research infrastructure



Ongoing

for optimal

Elettra 2.0

discussion at CNR

investments on

NRRP Italian Spin-OFF

Real Inffa-di

Piano Nazionale di Ripresa e Resilienza



4 partners – 9 nodes Polimi: nanofab AREA: TEM, hydrogen Unimi: surf. Magnetism CNR: nanofabs, ultrafast **Optics**, **TEM**

MP 3 : Digital Structur_e DIALS TAIN



6 : Virtual & Remote

WP 6 PR managemen Technology Transfer



industrial

Bridging academic & ir

N.

JAG FAIR data

JA4 Nanosafety

JA5 Nano

23 partners + 12 TP

186 methods 650 instruments

SR, Neutrons, EM



≥ 10

/Suo 101

10²

10¹

2012 2017 2018 2019 2020 2021 2022

since 2016: 93 papers on international journals, 29 with IF >9, 7 theses (Master, PhD)

SCIENCE at APE-LE

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Spin Texture of Topological Matter

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Electronic states in anomalous metals, low dimensional materials (graphene, topological insulators, transition metal dichalcogenides), highly correlated metallic oxides and 2D electron gases confined on surfaces/interfaces

Magnetic ordering and coupling in diluted magnetic systems, magnetic topological insulators; interfaces with ferromagnets; electronic/ magnetic properties of complex oxides and "out of equilibrium" systems

Fundamental aspects of photoemission spectroscopy, matrix element effects, dichroism

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Growth morphology, electron states and magnetism of **hybrid organic/inorganic interfaces**, charge transfer at the interfaces, doping effects on the molecular layer



Genuine Mott transition undressed of any symmetry breaking effects in thin films of V_2O_3



Spin polarized surface states in NiTe₂ exploited in high-frequency rectifiers



Binding energy (eV) Binding energy (eV)

Interplay between **magnetism and topological properties** in the axion insulator candidate EuSn₂P₂

Image: Stripping for the stripping of the s



SLS

Hisor

Elettra

Spin ARPES (Mott Cophee; SIS)

ARPES (Spectromicroscopy)

Spin ARPES (VLEED Espresso; BL9)

50 X 100 µm²

<1 µm (Schwarzschild; 27 & 74 eV)

~ 1 mm

 \sim

0.5

1.0

0

10

x (µm)

0.0

 $k_{v}(Å^{-1})$

-1.0 -0.5



since 2016: 91 papers, 26 with IF >9, 6 theses (Master, PhD)

Surface and Interface Magnetism / Multiferroism

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In-operando Ambient Pressure Spectroscopy



SCIENCE at APE-HE





ENHANCED PERFORMANCE: APE-EHE









Single domain XMCD/PES on Ferromagnets/multiferroics Magnetic dichroism in PES (LMDAD)

SR-facility	beamline	XAS/XMCD	in operando AP-XAS
Diamond	i10	XMCD, XMLD, 0.5-420 K, 14 T	
	B07 -		AP XAS for gas and liquid cells (300-450
	versox	XAS, XPS, 120-1250 K	K), AP-XPS up to 30 mbar, 250-750 K
		XMCD, XMLD, 2-350 K, 7 T, prep	
SLS	Xtreme	chamber	
		XMCD, XMLD, 0.2-370 (1000) K,	
Soleil	Deimos	7 (30) T, in situ	liquid cell for ferrofluids in FY
		XMCD (10 mT), XMLD, XPS, prep	
		chamber, 50-1200 K, time	
	Tempo	resolved	
		XMCD, XMLD, 3-325 K, 9 T, prep	
ESRF	ID32	chamber	
		XMCD, XMLD, 3-350 K, 6 T, prep	
Alba	Boreas	chamber	
		XMCD, XMLD, 0.3-500 K, 9 T,	
Bessy	Vekmag	time resolved	
ALS	4.0.2	XMCD, XMLD, 15-750 K, 4 T	
	932	200-900 eV XAS	200-900 eV, ambient pressure XPS



H-cell setup: in situ X-ray and IR spectroscopy





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RATIONALE:	1) electron mean free path varies from 0.5 to over 5 nm
	energy range favourable for PES/ARPES with depth sensitivity

- extending ARPES and core level photoemission spectroscopy from surface to bulk or buried layers allowing to probe **electron states**, graded compositions, multilayered devices
- access to 3rd and 4th period core edges (resonant photoemission and XAS/XMCD)
- in-operando setups

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2) Elettra 2.0 can host a **dedicated short insertion with performances well adapted** for bridging the soft-X to hard-X ranges (as IO9 of Diamond, but with a unique – short – undulator)

NANOSCOPIL 5,000 20, CRISTAL 000	Synchrotron	HAXPES	Energy range	
SAMBA	Soleil	HAXPES + RIXS (GALAXIES)	2.3-12 Kev	
ROXIMA (1 & 5,000 15,0	PETRA III	HAXPES (P22)	2.4-15 keV	
SWING 5,000 17,0	Diamond	HAXPES (109) 2 x > 2m undulators	0.1-20 keV	
5,000 20,0	Pessy	HAXPES (HIKE)	2.5 –12 keV	•
	Dessy	Ambient pressure HAXPES (Belchem-DCM, under cons	otr) 2.5-10 keV	
0.2 nm	SLS	Ambient pressure HAXPES endstation	N/A	

Benchmark IO9 vs. APE-TX

500 eV ~4x10^12 photon/s (slit 20um) 1000 eV ~ 3x10^12 photon/s (slit 10um)

2.5 keV ~1x10¹³ photon/s (Si(111) DCM) 2.5 keV ~ 3x10¹² photon/s (Si(111) DCM) 6 keV ~ 1.5x10¹² photon/s (Si(111) DCM) Example: critical thickness of 'metallic' bulk screening attenuation of bulk hybridization, localization of surface electrons.



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T. Pincelli et al. Nat. Comm. 8, 16051 (2017) IO9 – Diamond + BL19LXU Spring 8

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ARPES from Soft-X toTender-X

nature materials

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ARTICLES

PUBLISHED ONLINE: 14 OCTOBER 2012 | DOI: 10.1038/NMAT3/

Bulk electronic structure of the dilute magnetic semiconductor $Ga_{1-x}Mn_xAs$ through hard X-ray angle-resolved photoemission

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A. X. Gray^{1,2,3}*, J. Minár⁴, S. Ueda⁵, P. R. Stone^{2,6}, Y. Yamashita⁵, J. Fujii⁷, J. Braun⁴, L. Plucinski⁸, C. M. Schneider⁸, G. Panaccione⁷, H. Ebert⁴, O. D. Dubon^{2,6}, K. Kobayashi⁵ and C. S. Fadley^{1,2}



ARPES with 3.4 keV measured @ Spring-8



RESET

LRS

HRS



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A. Regoutz et al. Adv. Funct. Mater. 26, 507 (2016); C. Baumer et al. Faraday Discuss., (2019), 213;)



CONCEPT OF APE-Tender-X beamline

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Concept and construction by Bruno Diviacco



Preliminary concept under development by CNR and Elettra + international collaboration (IO9-like)



NFFA Prototype for AP-HAXPES experiment (collab. with 109) The sample volume is separated from the UHV by 2 SiN membranes (summer 2023).





• FIGURES OF MERIT OF THE APE-HIVE UPGRADES:

- APE-ELE : exploit beam brilliance for microfocussing, expand hv-range
- APE-EHE : exploit beam brilliance for for microfocussing and optimized 1st Harmonic source
- APE-TX : exploit Elettra 2.0 lattice (short section) and undulator technology to realize a continuous photon energy range for photoelectric effect measurements with variable (0.5 – 5 nm) depth sensitivity
- FAIR-by-design metadata acquisition -> towards ARWs in NFFA
- ONGOING DISCUSSION (2023) at CNR level for optimizing overall institutional investments on Elettra 2.0

Nanoscience research @ Elettra 2.0

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DigiMAT - Probing and controlling the electronic properties of materials by taking advantage of thin films technology

In-house	NFFA-TS		NFFA-Europe			
Bi ₂ Se ₃	* RE-doped SrTiO₃	* LaAlO₃	* V ₂ O ₃			
TiO ₂	* SrNbO₃	* Fe(Te _{0.5} Se _{0.5})	$*Fe-doped TiO_2$			
SrRuO ₃	* FeTe	* LaNiO₃	*TM-doped SrTiO $_3$			
La _{0.7} Ba _{0.3} MnO ₃	* Fe	* CaMnO₃	* BaTiO₃			
La _{0.7} Ce _{0.3} MnO ₃	* WO ₃	* Fe ₃ O ₄	RE-doped CeO ₂			
BiFeO₃	* LaVO₃	* MgGa ₂ O ₄	* RE-doped MgO			
WO ₃	* MoS ₂	* MgCr ₂ O ₄	* FeSe			
FeSe	* CeO ₂	* ZnO	* YSZ-8%			
V ₂ O ₃	* YBa2Cu3O7	* Bi ₂ WO ₆				
Cr ₄ Te ₅	$La_{0.7}Sr_{0.3}MnO_3$	* WO ₃				
	*MnSe2	* YIG - Y ₃ Fe ₅ O ₁₂				
*growth protocol developed "on-demand"						

36 different materials / 30 user-driven / 28 growth protocols developed

UV-ARPES experiments run on these materials





Dual pulsed laser deposition system for the growth of complex materials and heterostructures

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PLD – I (operational) UHV suitcase UHV transfer tube PLD – II (2021 NdYAG KrF laser DigiMAT